

AMENDMENTS TO THE SPECIFICATION

Please amend the paragraph bridging pages 18-19 as follows:

--Referring to Figure 1g, heat treatment is applied at a temperature close to or higher than the viscosity temperature. The main purpose of the heat treatment is to relax the stresses in the stressed layer 2. Heat treatment at a temperature higher than or around the viscosity temperature TG of the glassy layer 4 will cause the [[surface]] glassy layer to become viscous, which will allow the stressed layer to relax at its interface with the glassy layer 4, resulting in decompression of at least part of its internal stresses. Thus, if the glassy layer 4 is an SiO₂ layer created by thermal oxidization, heat treatment at a minimum of about 1,050°C, and preferably at about a minimum of 1,200°C for a predetermined duration, will cause relaxation or pseudo-relaxation of the stressed layer 2. The heat treatment typically lasts between a few seconds and several hours.--.